Design-Process-Technology Co-optimization for Manufacturability VIII

John L. Sturtevant
Luigi Capodieci
Editors

26–27 February 2014
San Jose, California, United States

Volume 9053

Printed in the United States of America.

Publication of record for individual papers is online in the SPIE Digital Library.

SPIEDigitalLibrary.org

Paper Numbering: Proceedings of SPIE follow an e-First publication model, with papers published first online and then in print and on CD-ROM. Papers are published as they are submitted and meet publication criteria. A unique, consistent, permanent citation identifier (CID) number is assigned to each article at the time of the first publication. Utilization of CIDs allows articles to be fully citable as soon as they are published online, and connects the same identifier to all online, print, and electronic versions of the publication. SPIE uses a six-digit CID article numbering system in which:
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Contents

iii

SESSION 3   **HOTSPOTS**

SESSION 4   **DESIGN OPTIMIZATION I**

SESSION 5   **PATTERN-AWARE TECHNIQUES: JOINT SESSION WITH CONFERENCES 9052 AND 9053**

v

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